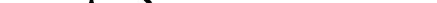


Substitute for form 1449A/PTO				<i>Complete if Known</i>	
<b>INFORMATION DISCLOSURE STATEMENT BY APPLICANT</b>				Application Number	
				Filing Date	
				First Named Inventor	Bing Lu et al.
				Group Art Unit	
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(use as many sheets as necessary)					
Sheet	1	of	1	Attorney Docket Number	SC12878TP

U. S. PATENT DOCUMENTS					
Examiner Initials*	Cite No. <sup>1</sup>	Document Number	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
		Number - Kind Code <sup>2</sup> (if known)			
AA	US - 2003/0031936 A1		02-13-2003	MANGAT	
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NON PATENT LITERATURE DOCUMENTS		
Examiner Initials*	Cite No. <sup>1</sup>	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.
	AG	LERCEL et al., "Etching Processes and Characteristics for the Fabrication of Refractory X-ray Masks," 1998 American Vacuum Society, J. Vac. Sci. Technol. B 16(6), Nov/Dec 1998, pp. 3577-3581.
	AH	BROOKS et al., "Characterization of Oxynitride Hardmask Removal Processes for Refractory X-ray Mask Fabrication," SPIE Vol. 3331, pp. 255-260 (1998).
	AI	DAUKSHER et al., "Uniform Low Stress Oxynitride Films for Application as Hardmasks on X-ray Masks," 1997 American Vacuum Society, J. Vac. Sci. Technol. B 15(6), Nov/Dec 1997, pp. 2232-2237.

Examiner Signature		Date Considered	7-25-05
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